Deposition Sources	**Resists**	**Developers**	**Solvents**
Sputter Targets	AZ 5214e (positive; can also be used for image reversal)	AZ 300 MIF	Acetone
Pt	SU-8 2025	SU-8 Developer	IPA
Al	SU-8 2050	AZ 726 MIF	Remover PG
SiO	SU-8 5		Ethyl Lactate
Ni	SU-8 100		MIBK
Cd (owned by Modestino Group)	SPR 220-3		Cyclopentanone
Ir	950 PMMA A6		Methanol
Ta	ma-N 2403		
Ti	MCC Primer 80/20 (HMDS)		
Ag	AZ 1512		
Cu (Owned by Ulman Group)	495 PMMA A4		
Pd (Owned by Ulman Group)			
Evaporation Pellets			
Cu			
Au			
Cr			
Al			
Ti			
ALD Precursors			
TMA (for Al_2O_3 deposition)			
TDMAH (for HfO_2 deposition)			